

REMARKS

Claims 26-32 and 36-43 are pending in this application. Claims 26 and 36 are amended herein. Claims 1-25, 33-35, and 45-57 were previously cancelled. Applicants respectfully request reconsideration of the claims in view of the following remarks.

Claims 26, 27, 28, 29, 30, 31 and 32 were rejected under 35 U.S.C. § 102(e) as being anticipated by Kim, et al. (U.S. Publication No. 2004/0084709; hereinafter referred to as "Kim").

Claim 26 is amended herein and now recites the limitation of "wherein a portion of the capacitor contact pad directly under the integrated capacitor and a portion of the capacitor contact pad directly under the capacitor contact pad contact form a continuous contact region." In an Office Action dated January 3, 2006, Examiner has referred to features 30, 32, 34 and 36 in Figure 1 of Kim as the integrated capacitor, and features 26a and 26b as the capacitor contact pad. In a telephonic interview held on August 23, 2006, Examiner has further identified feature 46b in Kim reference as the capacitor contact pad contact. Therefore, contact 26a is the portion of the capacitor contact pad directly under the integrated capacitor, and contact 26b is the portion of the capacitor contact pad directly under the capacitor contact pad contact. Please note that contacts 26a and 26b do not form a continuous contact region. As a matter of fact, contacts 26a and 26 are each connected to a source/drain region of a metal-oxide-semiconductor (MOS) transistor, whose gate stack is denoted as 11. Therefore, contacts 26a and 26b cannot possibly form a continuous contact region. Otherwise, the source region and the drain region of the MOS transistor will be shorted. For the above-discussed reasons, Kim lacks the limitation of "wherein a portion of the capacitor contact pad directly under the integrated capacitor and a portion of the capacitor contact pad directly under the capacitor contact pad contact form a

continuous contact region.” Claim 26 is thus allowable over Kim.

Claims 27-32 depend from claim 26. Applicants respectfully submit claims 27-32 are allowable over Kim for their dependence from claim 26, and for their further defining limitations.

Claims 36, 37, 38, 40, 41, 39, 42 and 43 were rejected under 35 U.S.C. § 102(e) as being anticipated by Kim.

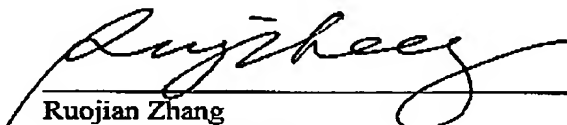
Claim 36 is amended herein and now recites the limitation of “wherein a portion of the capacitor contact pad directly under the integrated capacitor and a portion of the capacitor contact pad directly under the capacitor contact pad contact form a continuous contact region.” As discussed in the preceding paragraphs, contacts 26a and 26b in Kim are not continuous. Kim, Thus, lacks the limitation of “wherein a portion of the capacitor contact pad directly under the integrated capacitor and a portion of the capacitor contact pad directly under the capacitor contact pad contact form a continuous contact region.” Claim 36 is thus allowable over Kim.

Claims 37-39 and 42-43 depend from claim 36. Furthermore, claims 40-41 depend from claim 36. Applicants respectfully submit claims 37-43 are allowable over Kim for their dependence from claim 36, and for their further defining limitations.

Applicants have made a diligent effort to place the claims in condition for allowance. However, should there remain unresolved issues that require adverse action, it is respectfully requested that the Examiner telephone Ruojian Zhang, Applicants' Agent, at 972-732-1001 so that such issues may be resolved as expeditiously as possible. No fee is believed due in connection with this filing. However, should one be deemed due, the Commissioner is hereby authorized to charge, or credit any overpayment, to Deposit Account No. 50-1065.

Respectfully submitted,

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Date


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